

IN THE CLAIMS:

Please CANCEL Claim 3 without prejudice to or disclaimer of the subject matter recited therein.

Please AMEND claims 1, 2 and 5 as follows.

1. (Currently amended) An anti-vibration apparatus comprising:

a first permanent magnet unit ~~arranged on a support target and including a first permanent magnet~~ magnetized in a first direction perpendicular to a second direction in which a support target is supported; and

a second magnet unit including a pair of second permanent magnets, said pair of second permanent magnets being arranged ~~to interpose said first permanent magnet in noncontact without contact~~ with said first permanent magnet unit such that the same magnetic poles of said ~~first and second permanent magnet magnets~~ oppose each other through said first permanent magnet unit,

wherein sizes of said first permanent magnet unit and said second magnet ~~units~~ unit are set such that no force acts between said first permanent magnet unit and said second magnet ~~units~~ unit in a relative ~~position~~ positional range between said first permanent magnet unit and said second magnet ~~units~~ unit in a third direction perpendicular to ~~a direction in which said first magnet unit supports the support target~~ the first and second directions.

2. (Currently amended) The apparatus according to claim 1, wherein the size of said first permanent magnet unit is smaller than those of said pair of second permanent magnets in a the third direction perpendicular to the ~~support~~ first direction and the ~~opposing~~ second direction.

Claim 3 (cancelled)

4. (Original) The apparatus according to claim 1, further comprising an electromagnetic actuator for generating a force which acts on the support target.

5. (Currently amended) The apparatus according to claim 1, wherein said second magnet unit includes a changing unit which changes an area through which said pair of second permanent magnets ~~oppose~~ opposes said first permanent magnet unit.

6. (Original) The apparatus according to claim 5, wherein said changing unit changes the area based on a position of an object on the support target.

7. (Original) A device manufacturing apparatus comprising an anti-vibration apparatus defined in claim 1.

8. (Original) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising an anti-vibration apparatus and a support target defined in claim 1.

9. (Original) The apparatus according to claim 8, wherein at least one of a stage for a reticle, a stage for a substrate to be exposed, and a system which projects the pattern is arranged on said support target.

10. (Original) The apparatus according to claim 8, wherein said exposure apparatus is arranged in a vacuum chamber.

11. (Original) A device manufacturing method comprising a step of using an anti-vibration apparatus defined in claim 1.

12. (Original) A device manufacturing method comprising a step of exposing a substrate to a pattern using an exposure apparatus defined in claim 8.